



Patent  
Attorney's Docket No. 015290-458

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of )  
 )  
Christopher C. CHANG et al. ) Group Art Unit: 1773  
 )  
Application No.: 09/749,917 ) Examiner: N. Uhler  
 )  
Filed: December 29, 2000 ) Confirmation No.: 6832  
 )  
For: LOW CONTAMINATION PLASMA )  
CHAMBER COMPONENTS AND )  
METHODS FOR MAKING THE SAME )

AMENDMENT TRANSMITTAL LETTER

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Enclosed is an Amendment for the above-identified patent application.

- ☐ A Petition for Extension of Time is also enclosed.
- ☐ A Terminal Disclaimer and the ☐ \$55.00 (2814) ☐ \$110.00 (1814) fee due under 37 C.F.R. § 1.20(d) are also enclosed.
- ☐ Also enclosed is/are \_\_\_\_\_
- ☐ Small entity status is hereby claimed.
- ☐ Applicant(s) request continued examination under 37 C.F.R. § 1.114 and enclose the ☐ \$375.00 (2801) ☐ \$750.00 (1801) fee due under 37 C.F.R. § 1.17(e).
- ☐ Applicant(s) previously submitted \_\_\_, on \_\_\_, for which continued examination is requested.
- ☐ Applicant(s) request suspension of action by the Office until at least \_\_\_, which does not exceed three months from the filing of this RCE, in accordance with 37 C.F.R. § 1.103(c). The required fee under 37 C.F.R. § 1.17(i) is enclosed.
- ☐ A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) (1809/2809) is also enclosed.
- ☐ No additional claim fee is required.

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☒ An additional claim fee is required, and is calculated as shown below:

| AMENDED CLAIMS   |               |   |              |                    |            |
|--|---------------|---|--------------|--------------------|------------|
|  | NO. OF CLAIMS | HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR | EXTRA CLAIMS | RATE               | ADDT'L FEE |
| Total Claims   | 36            | MINUS 39 =                                | 0            | × \$18.00 (1202) = | -0-        |
| Independent Claims   | 7             | MINUS 5 =                                 | 2            | × \$84.00 (1201) = | \$168.00   |
| If Amendment adds multiple dependent claims, add \$280.00 (1203)       |               |   |              |                    |            |
| Total Amendment Fee  |               |   |              |                    | \$168.00   |
| If small entity status is claimed, subtract 50% of Total Amendment Fee |               |   |              |                    |            |
| TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT                            |               |   |              |                    | \$168.00   |

☒ A claim fee in the amount of \$ 168.00 is enclosed.

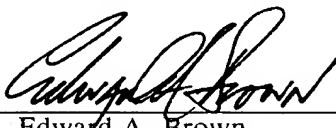
☐ Charge \$ \_\_\_\_\_ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17, 1.20(d) and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By: \_\_\_\_\_

  
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Date: March 24, 2003



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Washington, D.C. 20231

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Sir:

In response to the Official Action dated January 27, 2003, please amend the above-identified application as follows.

IN THE CLAIMS:

Please cancel Claims 18, 37 and 38 without prejudice to or disclaimer of the subject matter contained therein, and replace Claims 14, 16, 17, 27 and 34, as follows:

14. (Twice Amended) A component of a plasma reactor, the component being selected from the group consisting of a plasma confinement ring, a focus ring, a pedestal, a chamber wall, a chamber liner and a gas distribution plate, the component having one or more surfaces exposed to the plasma during processing, the component comprising an as-sprayed plasma sprayed coating on a plasma exposed surface of the component, the